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09/518,842INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

(Use several sheets if necessary)

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ConklinFiling Date:
March 3, 2000Group:
1647

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
BB	A1	97/16549	05/09/97	PCT		
	A2	95/34653	12/21/95	PCT		

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Patents, etc.)

BB	A3	---	Koman et al., J. Biol. Chem. 271: 20238-20241, 1996.
	A4	---	Hillier et al., WashU-Merck EST Project, Accession No. H02449, 1995.
	A5	---	Hillier et al., WashU-Merck EST Project, Accession No. R16073, 1995.
	A6	---	Hillier et al., WashU-Merck EST Project, Accession No. R31278, 1995.
	A7	---	Hillier et al., WashU-Merck EST Project, Accession No. R31794, 1995.
	A8	---	Hillier et al., WashU-Merck EST Project, Accession No. R62136, 1995.
	A9	---	Hillier et al., WashU-Merck EST Project, Accession No. R62240, 1995.
	A10	---	Hillier et al., WashU-Merck EST Project, Accession No. R67799, 1995.
	A11	---	Hillier et al., WashU-Merck EST Project, Accession No. R68426, 1995.
	A12	---	Hillier et al., WashU-Merck EST Project, Accession No. R77100, 1995.
	A13	---	Hillier et al., WashU-Merck EST Project, Accession No. R75651, 1995.
	A14	---	Hillier et al., WashU-Merck EST Project, Accession No. R77804, 1995.
BB	A15	---	Hillier et al., WashU-Merck EST Project, Accession No. H02448, 1995.

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Examiner

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Date considered

7/11/2001

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